

Title (en)

GALVANIC BATH OR MIXTURE FOR USE IN A GALVANIC BATH FOR DEPOSITING A GLOSS NICKEL LAYER AND METHOD FOR PRODUCING AN ITEM WITH A GLOSS NICKEL LAYER

Title (de)

GALVANISCHES BAD ODER MISCHUNG ZUR VERWENDUNG IN EINEM GALVANISCHEN BAD ZUR ABSCHIEDUNG EINER GLANZNICKELSCHICHT SOWIE VERFAHREN ZUR HERSTELLUNG EINES ARTIKELS MIT EINER GLANZNICKELSCHICHT

Title (fr)

BAIN GALVANIQUE OU MÉLANGE À UTILISER DANS UN BAIN GALVANIQUE POUR LA SÉPARATION D'UNE COUCHE DE NICKEL BRILLANT ET PROCÉDÉ DE PRODUCTION D'UN ARTICLE DOTÉ D'UNE COUCHE DE NICKEL BRILLANT

Publication

EP 2937450 B1 20170405 (DE)

Application

EP 15164491 A 20150421

Priority

DE 102014207778 A 20140425

Abstract (en)

[origin: JP2015212417A] PROBLEM TO BE SOLVED: To provide an electrolytic bath for production of a bright nickel layer on a constituent element of a part for a water conduit tube and a mixture for use in an electrolytic bath. SOLUTION: An electrolytic bath or a mixture comprises (c) benzoic acid sulfimide and/or benzoic acid sulfimide anion, (h) one or more or all the compounds selected from chloral hydrate, bromal hydrate, formic acid, formate, acetic acid, acetate and substituted/unsubstituted aliphatic aldehydes, (a) nickel ion, (b) one or more acids, (e) one or more acetylene-based unsaturated compounds of formula (I), (f) one or more betaines of formula (II) and (g) one or more humectants.

IPC 8 full level

C25D 3/18 (2006.01); **C25D 3/12** (2006.01); **C25D 3/16** (2006.01); **C25D 5/14** (2006.01)

CPC (source: EP)

C25D 3/16 (2013.01); **C25D 3/18** (2013.01)

Citation (opposition)

Opponent : ATOTECH

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DOCDB simple family (application)

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